

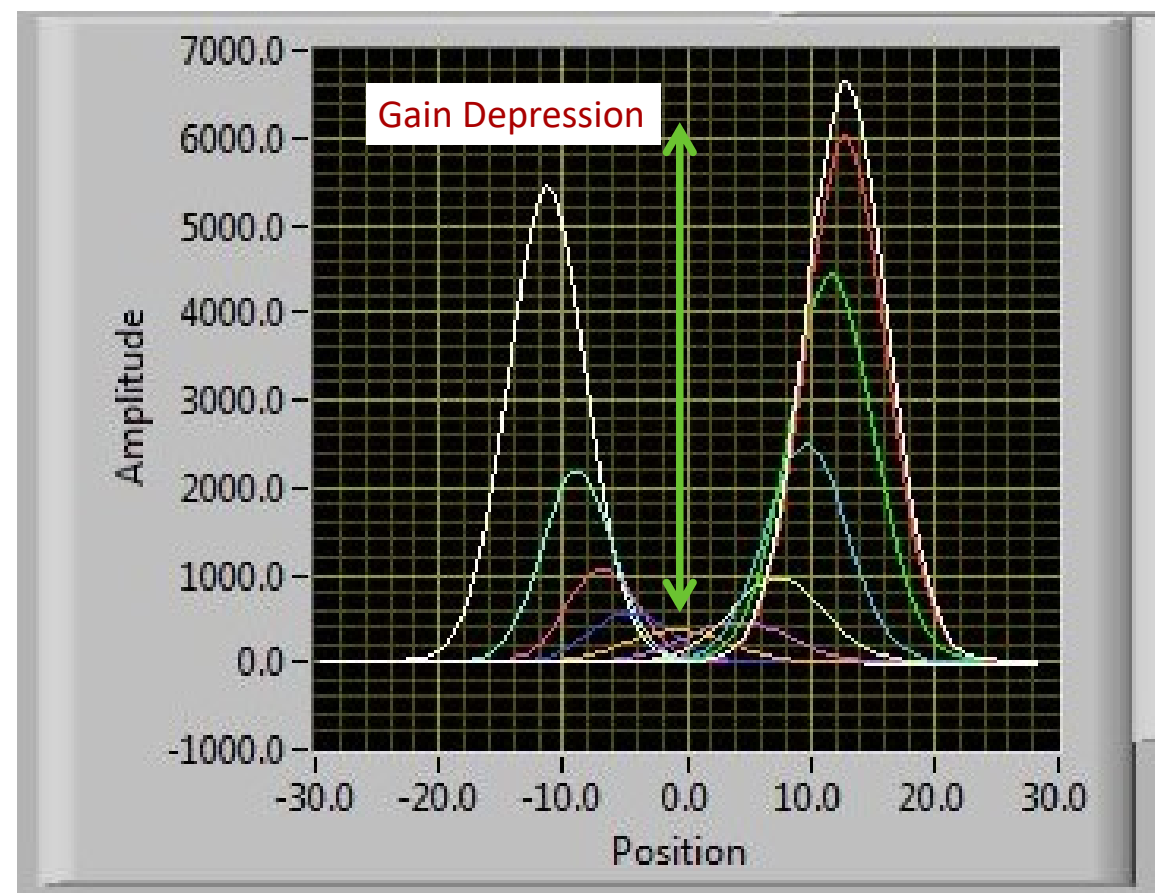
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Abstract
One of the on-going issues with the use of microchannel plates (MCP) in the ionization profile monitors (IPM) at Fermilab is the significant decrease in gain over time. There are several possible issues that can cause this. Historically, the assumption has been that this is aging, where the secondary emission yield (SEY) of the pore surface changes after some amount of extracted charge. Recent literature searches have brought to light the possibility that this is an initial 'scrubbing' effect whereby adsorbed gases are removed from the MCP pores by the removal of charge from the MCP. This paper discusses the results of studies conducted on the IPMs in the Main Injector at Fermilab.

Introduction

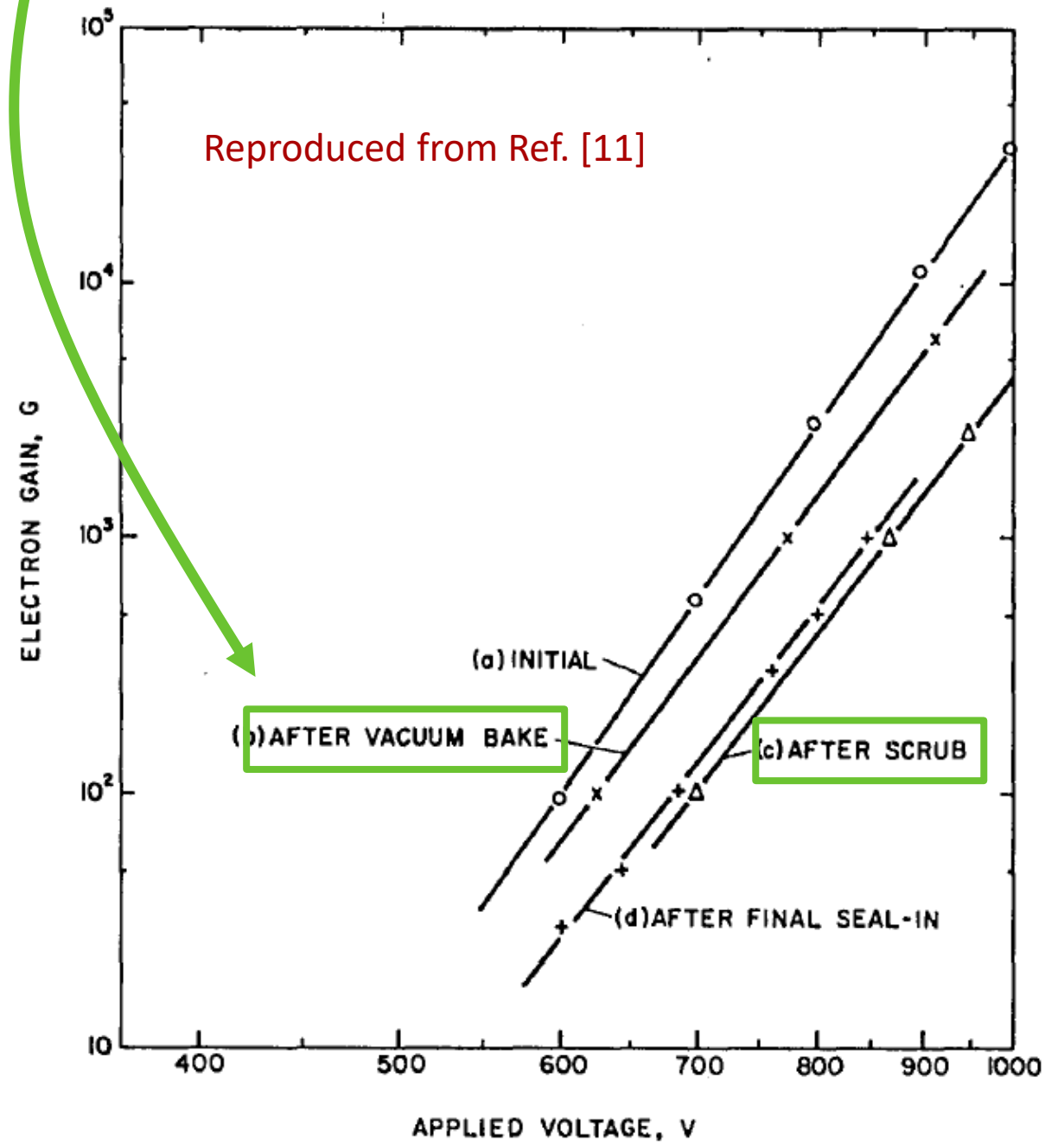
Ionization profile monitors (IPM) are used in many accelerator laboratories around the world [1-7]. They have been used in nearly all the synchrotrons built at Fermilab, and presently are used in the Main Injector (MI), Recycler Ring (RR), and Booster synchrotron [8], with another one being planned for the Integral Optics Test Accelerator (IOTA). All Fermilab IPMs, as well as many of those at other laboratories, utilize one or more microchannel plates (MCP) for signal amplification. Historically we have found that the gain of the MCP decreases over time and have attributed it to the well-known fact that they age with current extracted from them [9]. Thus, we have periodically replaced them. Recently, more in-depth investigations have revealed that the decrease in the gain is much more consistent with conditioning, or 'scrubbing', of the MCPs, and not aging. Literature searches have rediscovered the fact that a decrease in gain with conditioning is a known property of MCPs [10,11]. Our own historical IPM data and a recent dedicated test show results which are much more consistent with what one expects from conditioning.

Scan of gain over the MCP showing the drop in gain where the beam is normally positioned



Previous MCP Literature

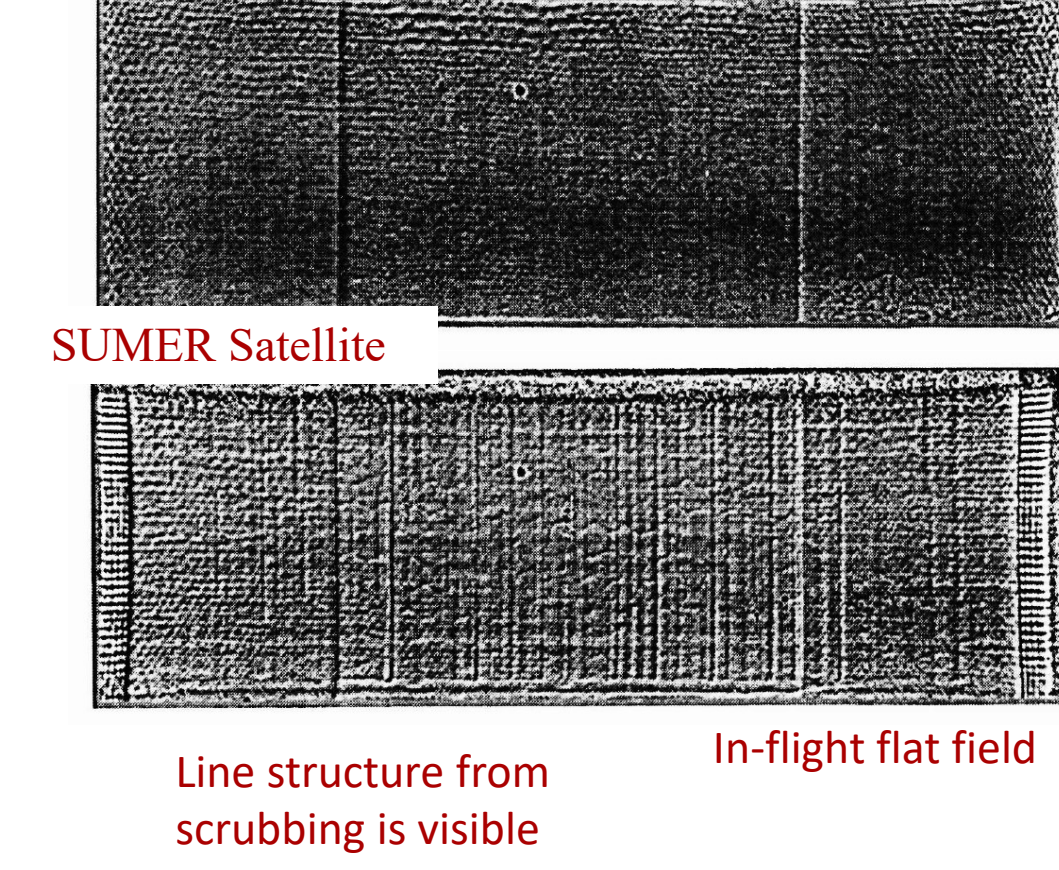
Measured gain of an MCP (taken from [11]) at various stages in the preparation: initial, after vacuum bake, after scrub, and after final seal-in. The gain decrease from after vacuum bake to after scrub is a factor of 3. Scrubbing refers to the initial phase of operation of the MCP, where the electrons act to ionize adsorbed gases and remove them from the surfaces of the pores.



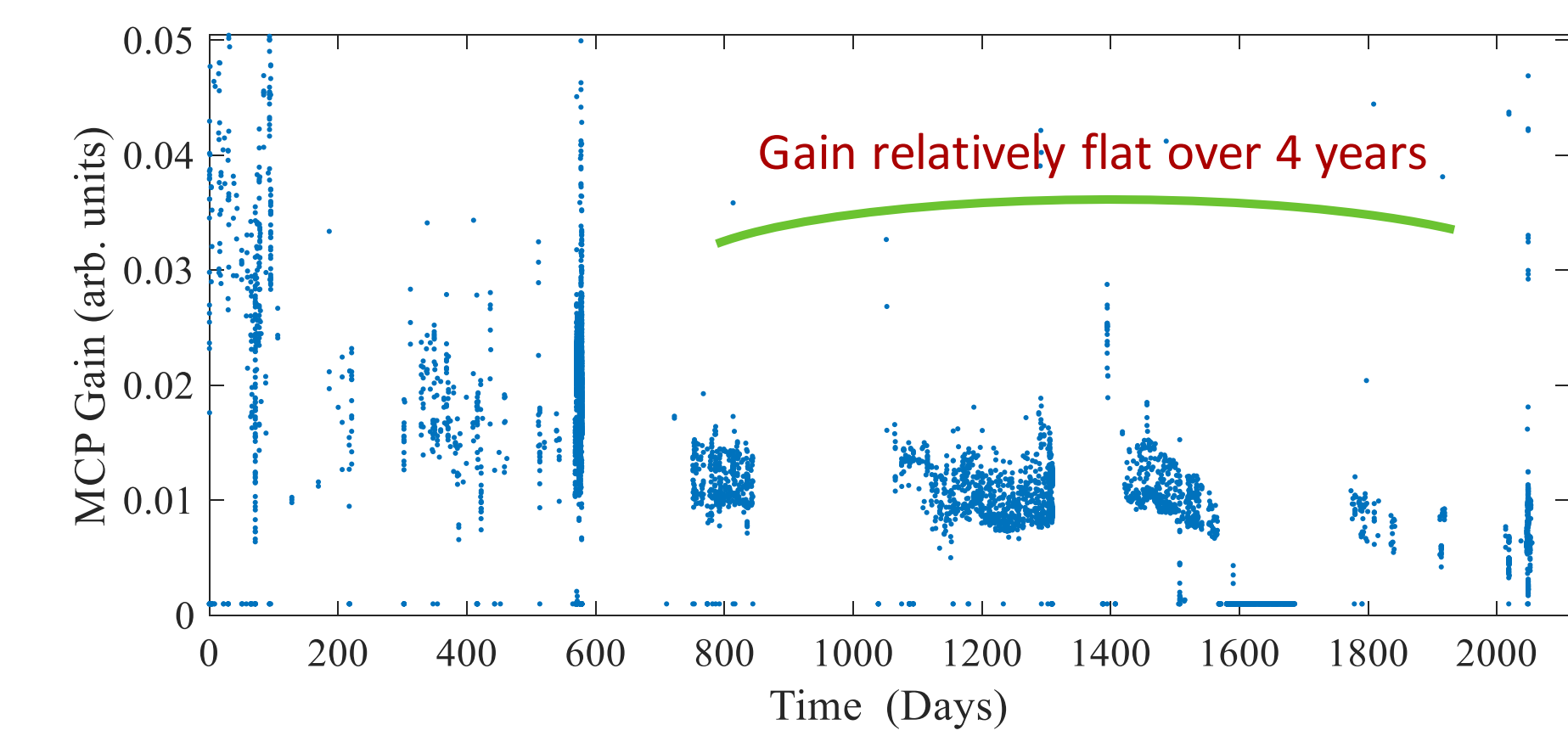
MCPs can be conditioned by illumination with ultraviolet radiation until the gain stabilizes [10]. Whether or not the MCP can be exposed to atmosphere after conditioning without losing the benefits of the conditioning is not yet entirely clear to us [15,16].

The lifetime of a MCP is generally $> 1 \text{ C/cm}^2$. Conditioning of the MCP happens much faster than that, typically less than 0.1 C/cm^2 [9,19,21].

Reproduced from Ref. [17] Pre-flight flat field

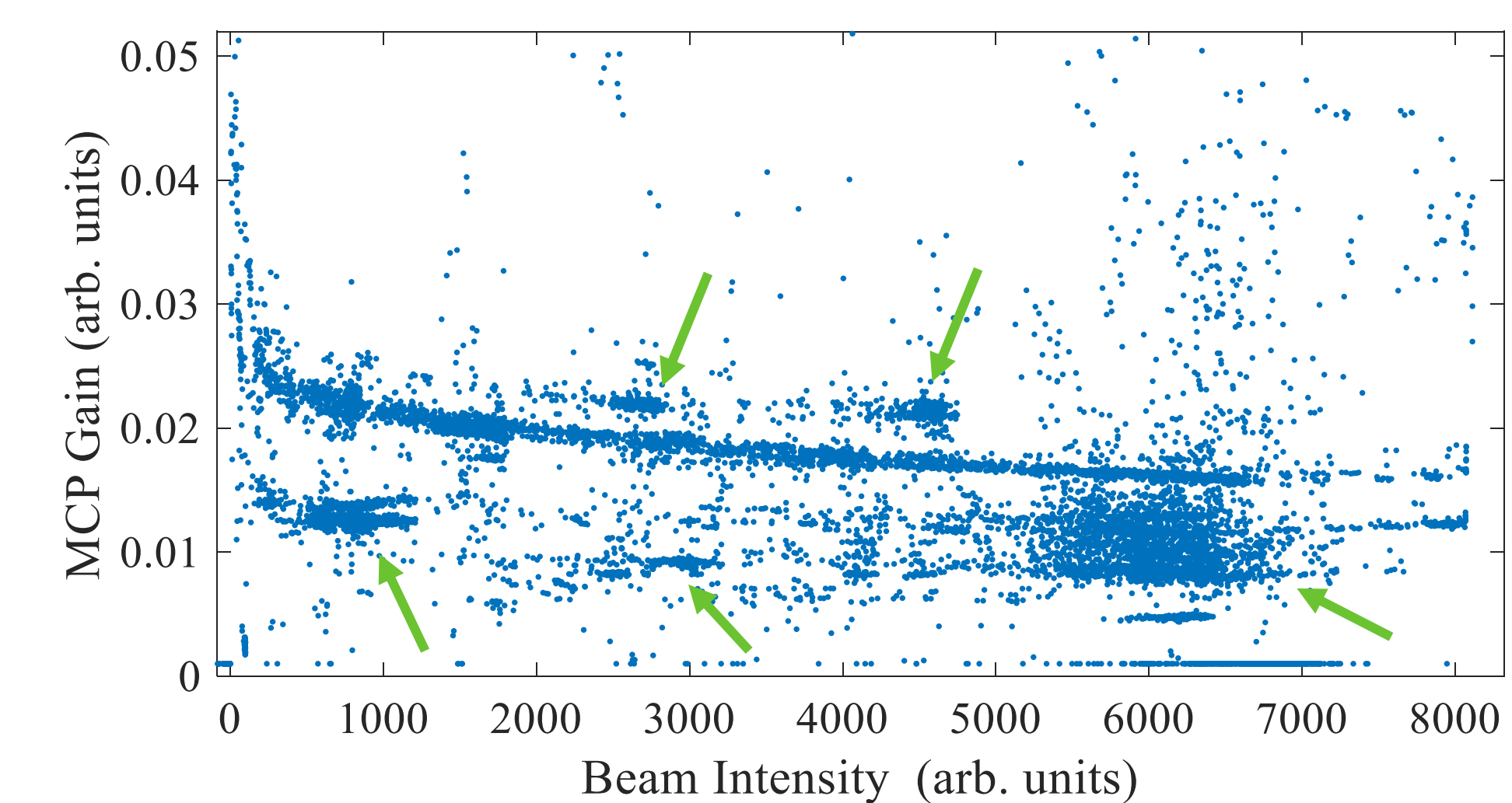


The use of MCPs in satellites encounters similar gain issues as we do with the IPMs [17-19]. When used in a spectrometer, spectral lines are placed at defined positions on the MCP. As it is apparently impractical [16] to keep a satellite MCP under vacuum, the initial operation of it in space causes the brighter lines to scrub faster resulting in a non-uniform gain, just as the beam in an accelerator is always located at the same location and produces a dip in the gain.



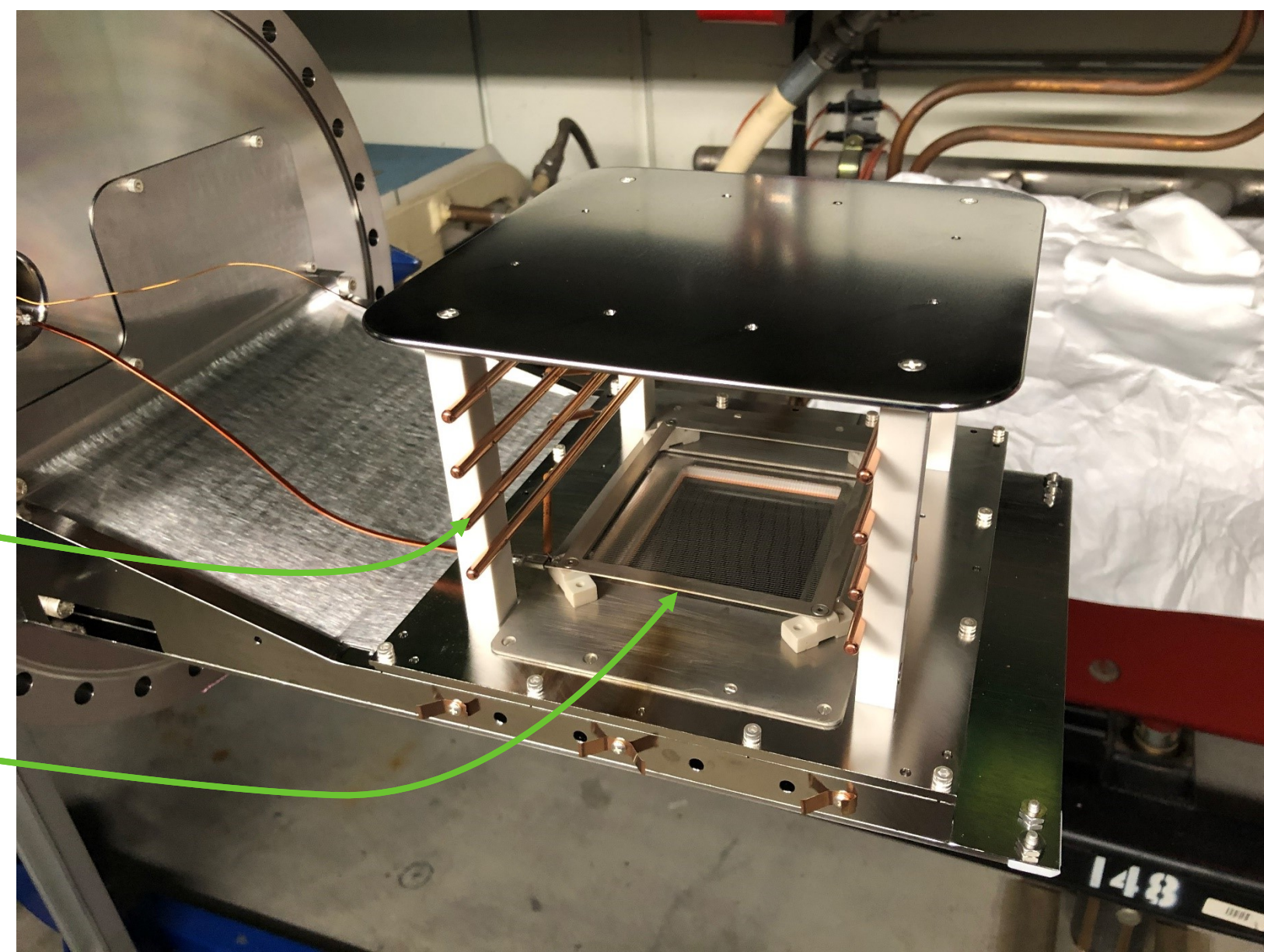
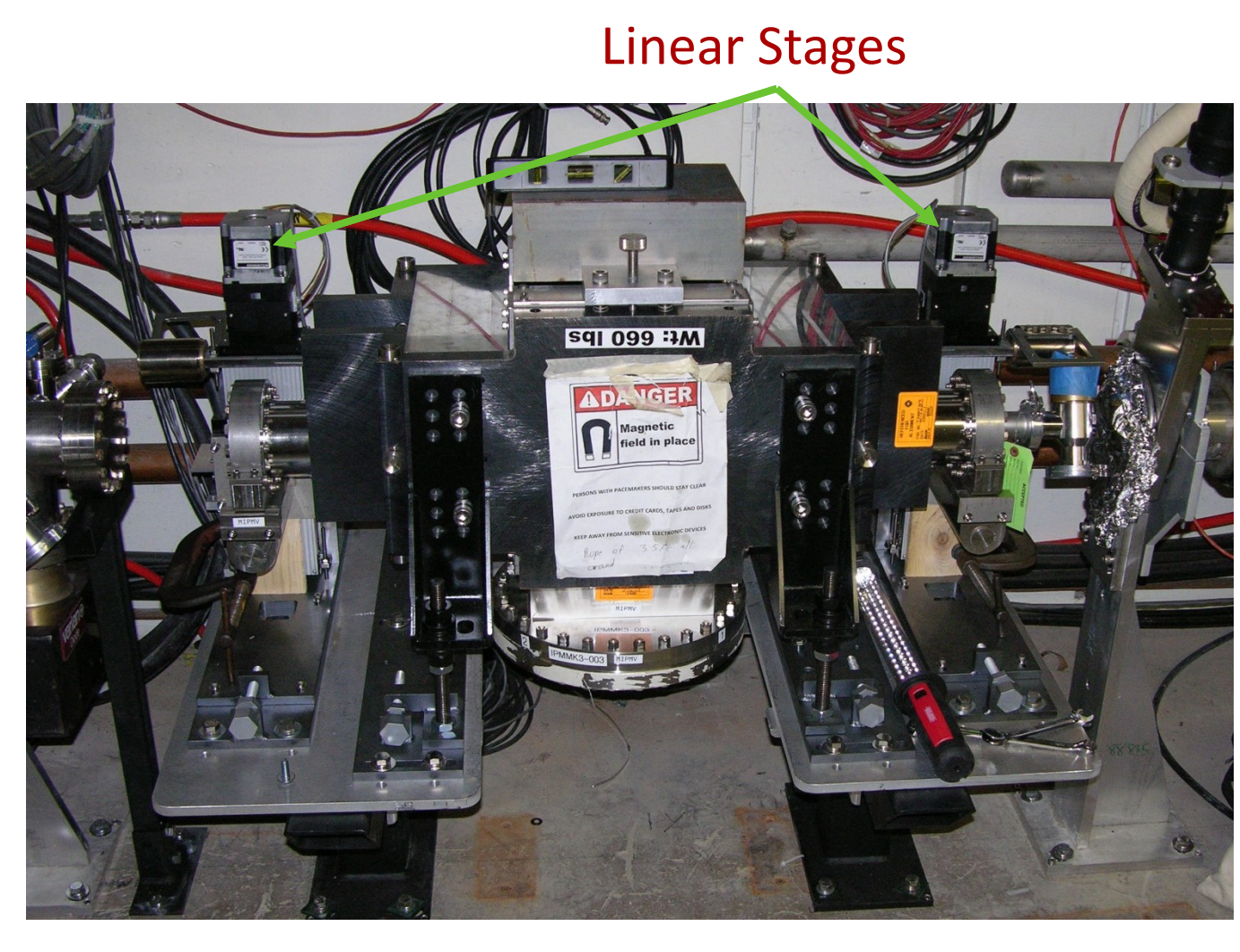
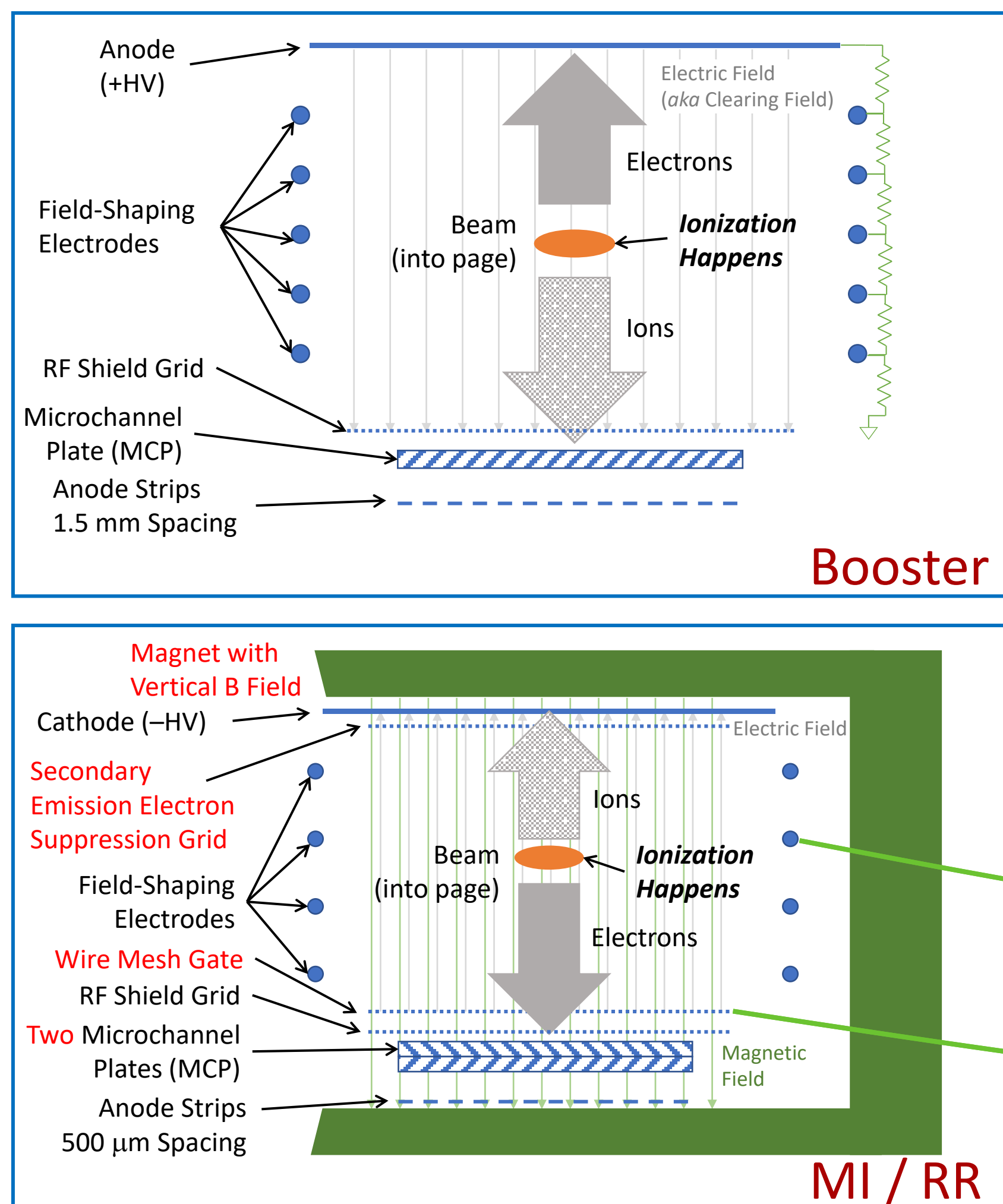
Gain relatively flat over 4 years.

Historical MCP gain resulting from the scaling by beam intensities and the voltage gain curve. It would appear that the MCP gain decreased after initial installation but has been relatively flat after that. This is a behavior consistent with initial conditioning, and not aging.

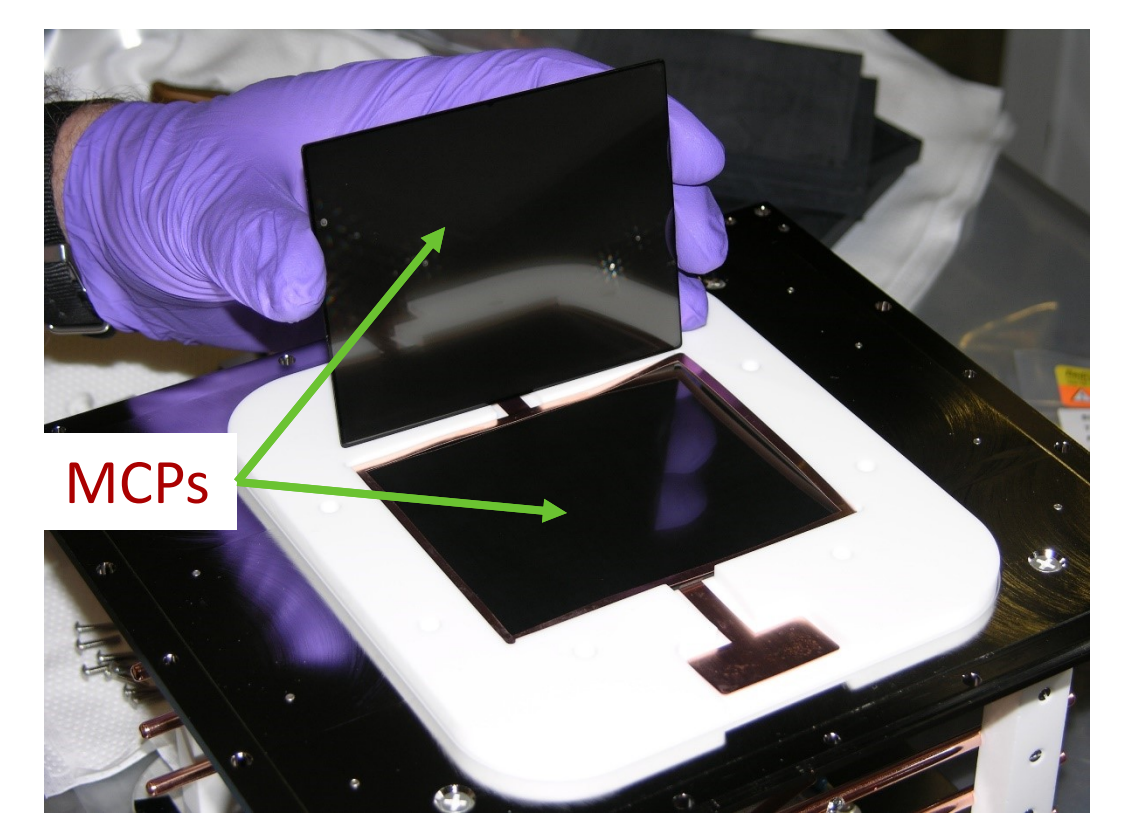
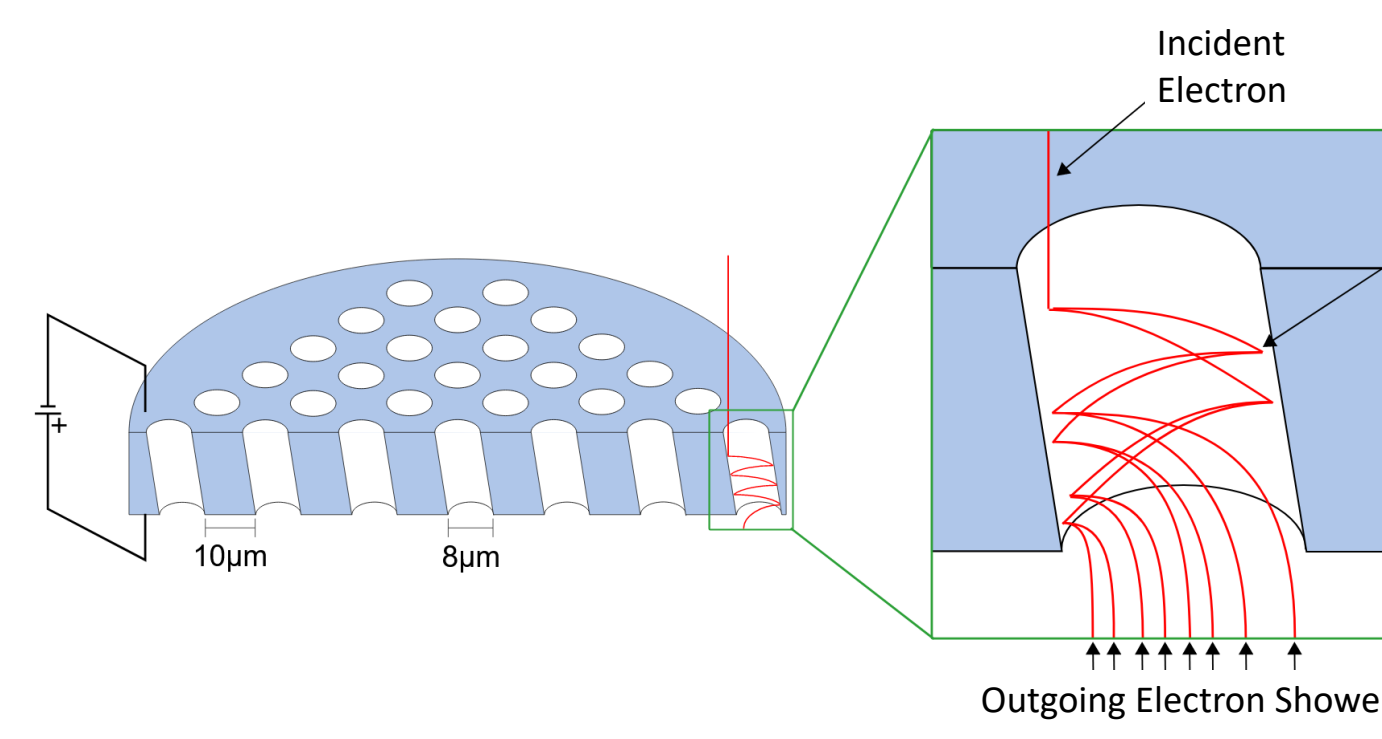


MCP gain vs. beam intensity after scaling for beam intensity. It is not flat and there are various isolated regions (some indicated by green arrows) that need to be understood.

Experimental Devices

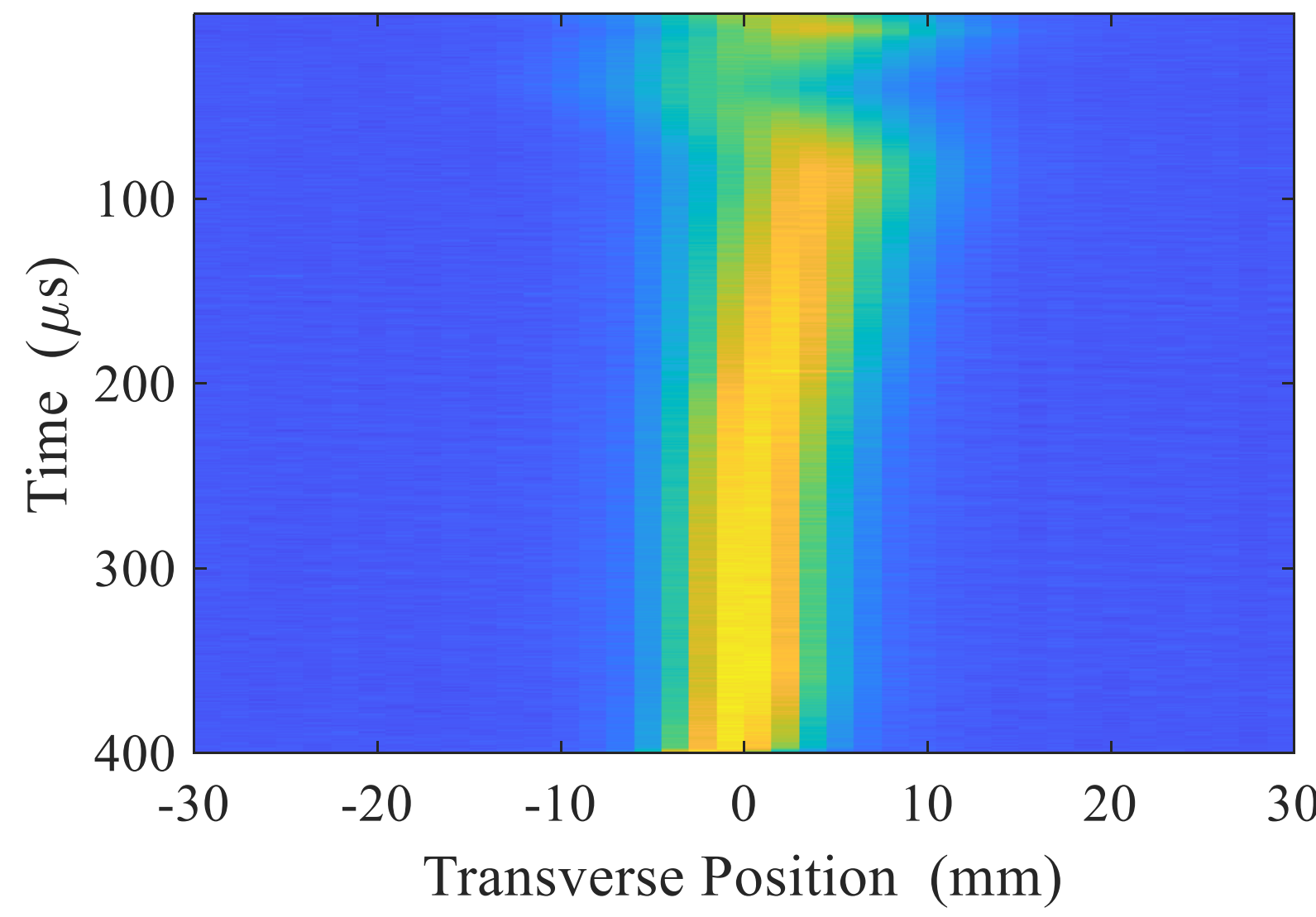


MCP
Schematic of MCP functional behavior showing amplification by electron avalanche.

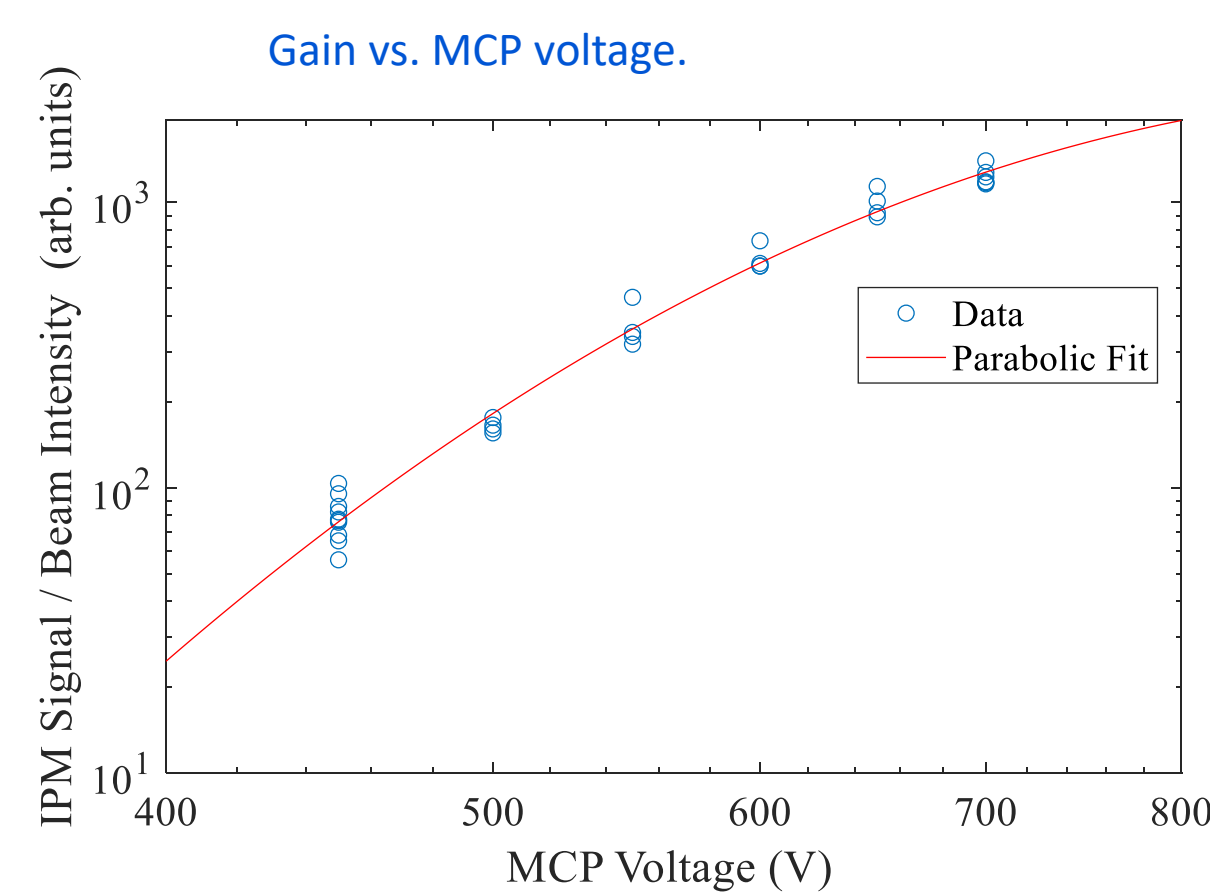


Historical Booster Data

Booster IPM signal from injection (top) to extraction (bottom).

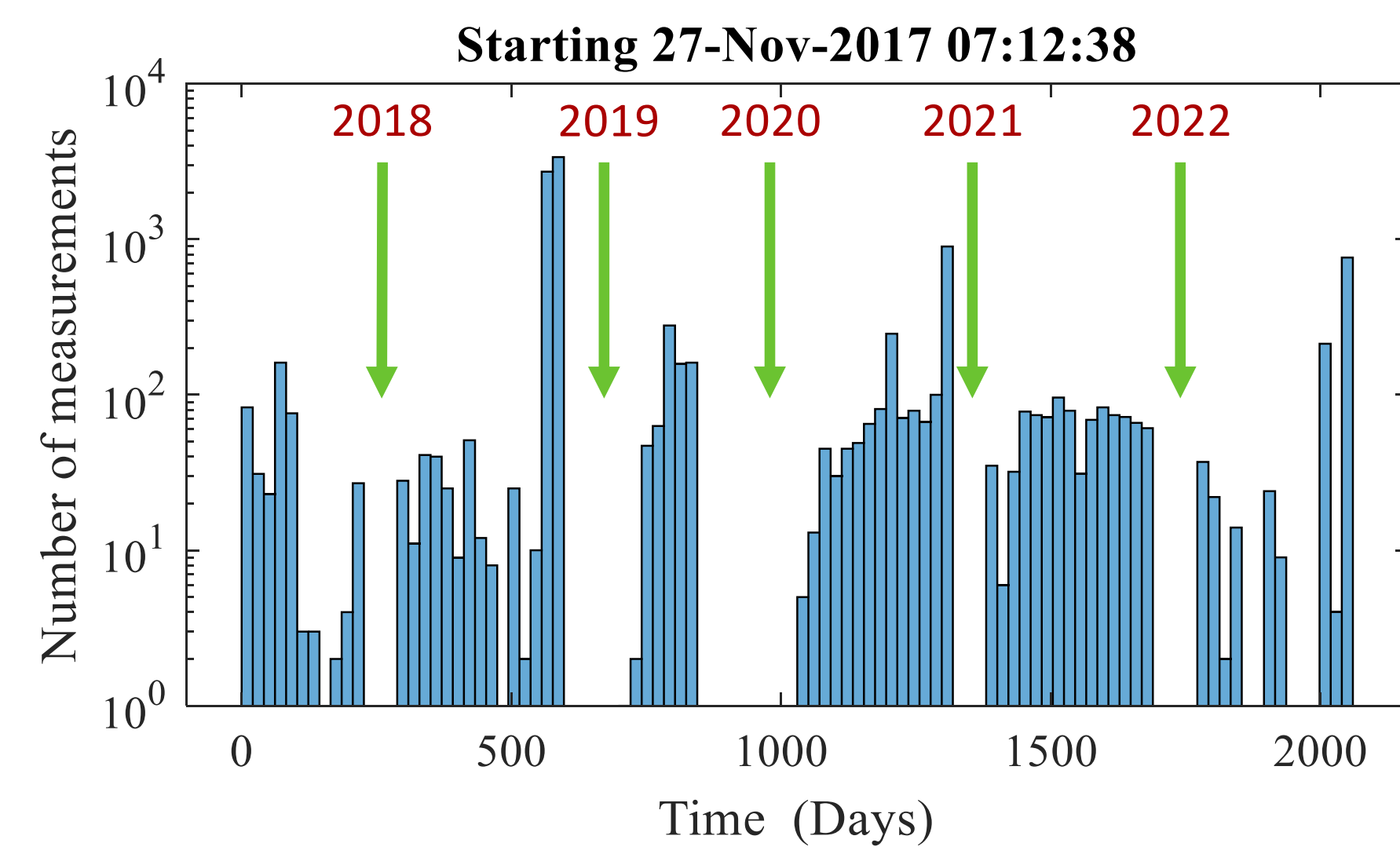


The MCP was moved to a new region of the plate, and then run repeatedly for a period of ~5 days. MI IPM signal from injection (top) to extraction (bottom).

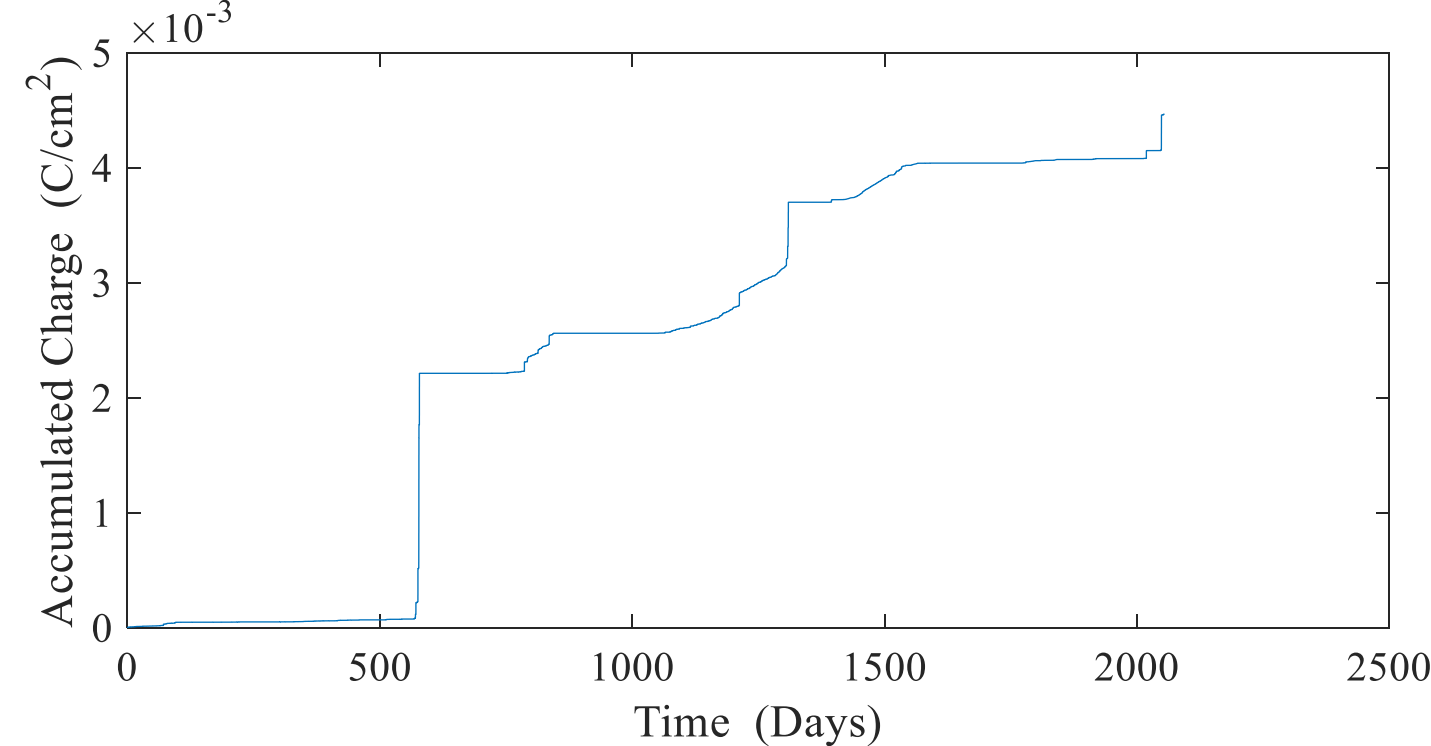


The raw IPM integrated signals and the beam intensities. During the 5 days, the voltage was periodically adjusted to keep the signals at similar levels. This is indicated by the vertical magenta lines. The processing corrected for the changes in voltage by scaling the data in each voltage region to match at the boundaries.

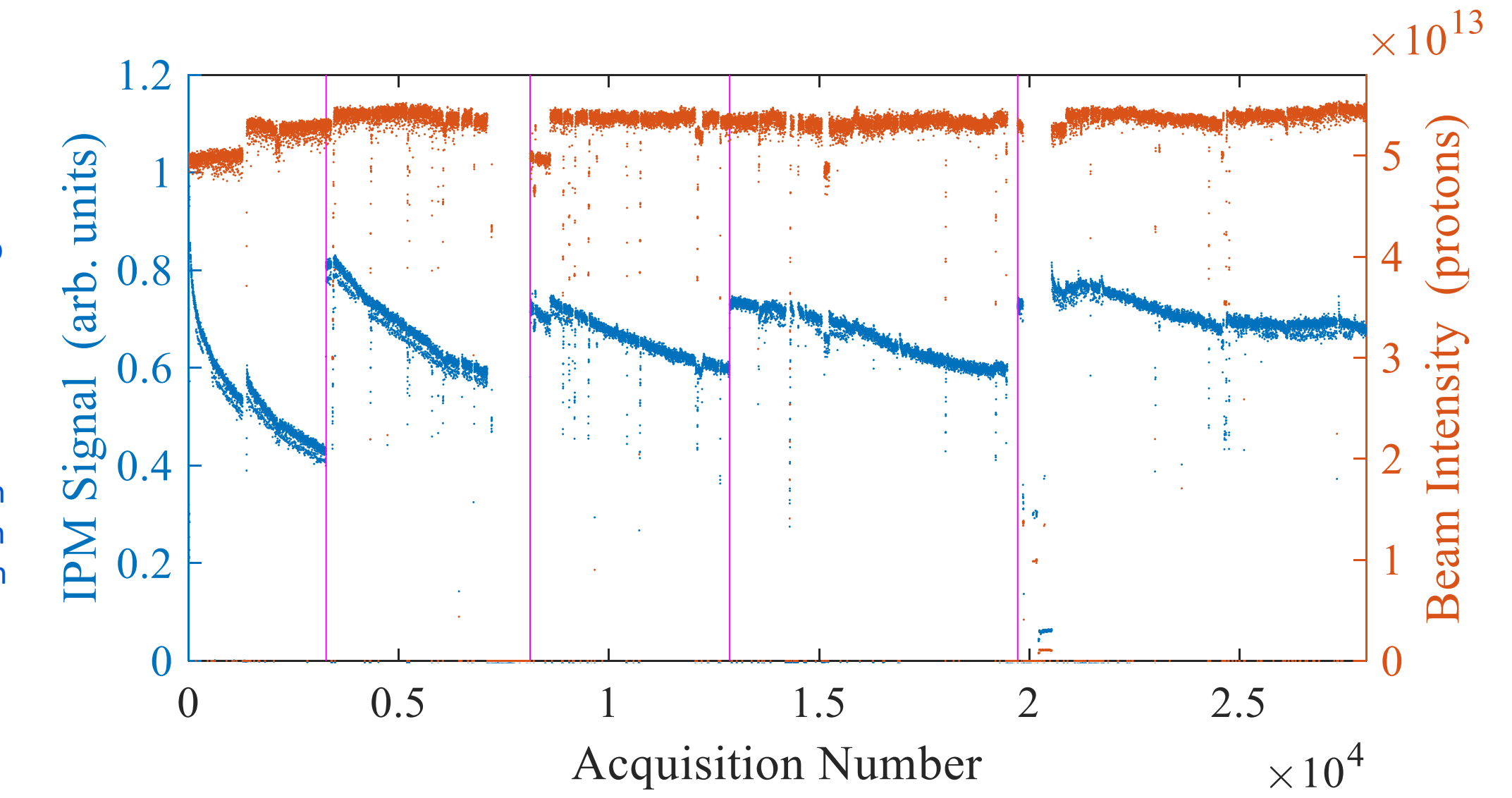
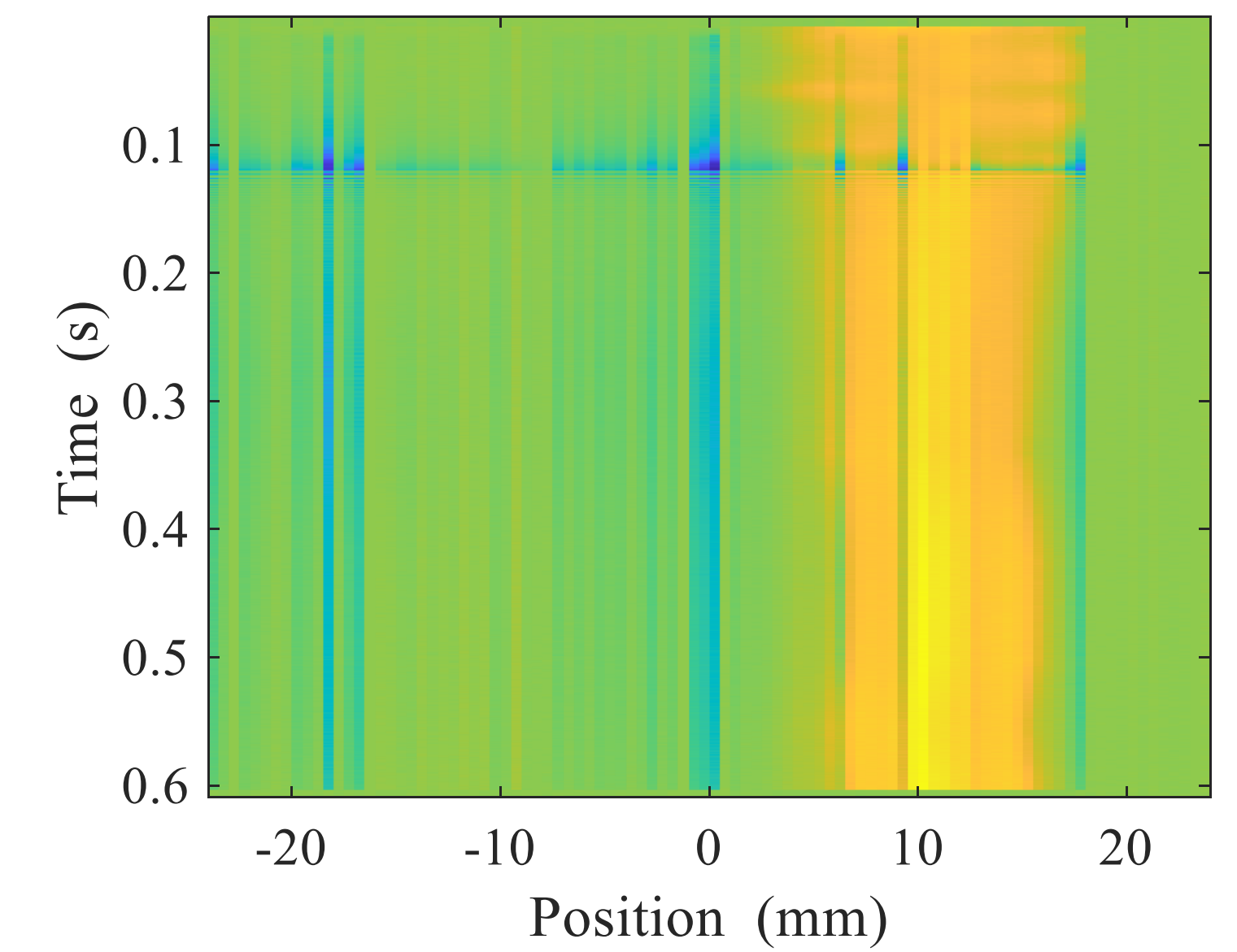
The distribution of Booster IPM acquisitions as a function of time. We calculated the MCP gain from this data by scaling it by the beam intensity and by the voltage gain curve above. Red arrows indicate maintenance periods.



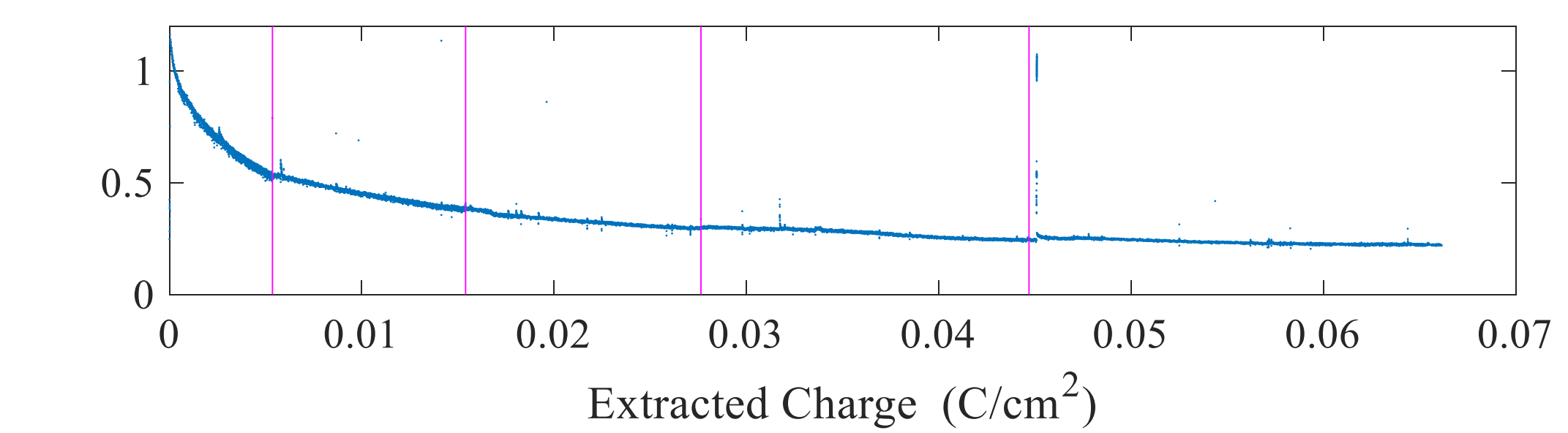
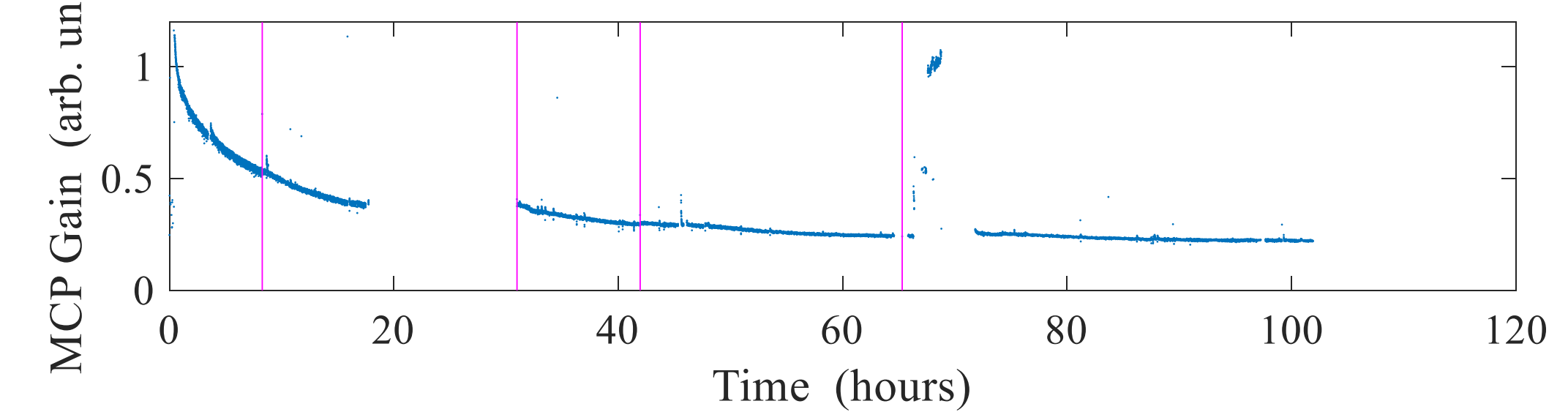
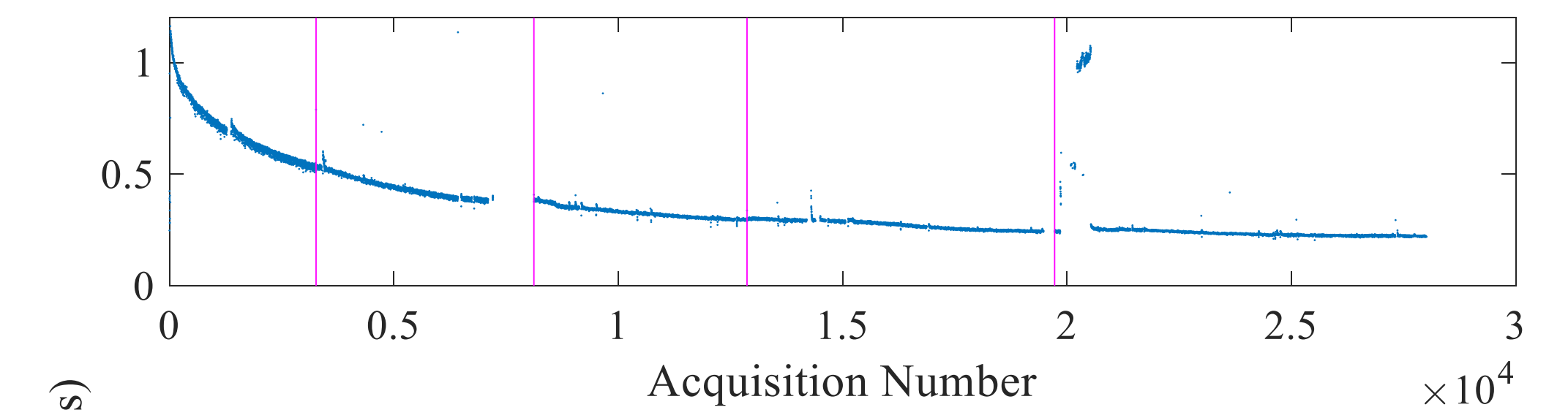
Since the MCP should age with extracted charge, we calculate the extracted charge for an acquisition as $Q = ITD$, where I is the average current from the MCP during the acquisition, T is the time the high voltage is on (~3 seconds), and D is the Booster duty cycle (~50%). Shown here is the integral of the extracted charge vs. time which is a little over 4 mC/cm^2 , not yet near the level where aging would be a concern.



Main Injector Study



Processing of the data corrected for the beam intensity and accounted for the changes in voltage by scaling the data in each voltage region to match at the boundaries. Shows this gain as a function of acquisition number, time, and integrated charge out of the MCP. Here as well, the change in gain is consistent with scrubbing, not with aging. One additional thing to note is that since the MI/RR IPMs have a pair of MCPs, the scrubbing is mostly affecting the second MCP which has much higher current draw.



REFERENCES

- [1] K. Satou, "Development of a gated IPM system for J-PARC MR", in *Proc. IBIC'19*, Malmö, Sweden, Sep. 2019, pp. 343-346. doi:10.18429/IAACW-IBIC2019-TUPP020
- [2] H.S. Sandberg *et al.*, "Commissioning of Timepix3 based beam gas ionisation profile monitors for the CERN Proton Synchrotron", in *Proc. IBIC'21*, Pohang, Rep. of Korea, May 2021, pp. 172-175. doi:10.18429/IAACW-IBIC2021-TU0A05
- [3] A. Jansson *et al.*, "IPM measurements in the Tevatron", in *Proc. PAC'07*, Albuquerque, NM, USA, June 2007, pp. 3883-3885. doi:10.1109/PAC.2007.4440026
- [4] M. Sachwitz *et al.*, "IPM measurements in the Tevatron", in *Proc. PAC'07*, Albuquerque, NM, USA, June 2007, pp. 3883-3885. doi:10.1109/PAC.2007.4440026
- [5] R. Conolly, J. Fite, S. Jao, S. Tepikian and C. Trabocchi, "Residual-gas-ionization beam profile monitors in RHIC", in *Proc. EPAC'08*, Genoa, Italy, June 2008, pp. 1266-1268. https://accelconf.web.cern.ch/epac08/papers/tupc090.pdf
- [6] K. Wittenburg, "Experience with the residual gas ionization beam profile monitors at the DESY proton accelerators", in *Proc. EPAC'92*, Berlin, Germany, Mar. 1992, pp.1133-1135. https://accelconf.web.cern.ch/epac92/PDF/EPAC1992_1133.PDF
- [7] F. Benedetti *et al.*, "Design and development of ionization profile monitor for the cryogenic sections of the ESS linac", *EPL Web Conf.*, vol. 225, p. 01009, 2020. doi:10.1051/epjconf/202022501009
- [8] J.R. Zagel *et al.*, "Third generation residual gas ionization profile monitors at Fermilab", in *Proc. IBIC'14*, Monterey, CA, USA, Sep. 2014, pp. 408-411. https://jacow.org/IBIC2014/papers/tup04.pdf
- [9] B.R. Sandel, A. Lyle Broadfoot and D. E. Schemansky, "Microchannel plate life tests", *Appl. Opt.*, vol. 16, no. 5, 1977, pp. 1435-1437. doi:10.1364/AO.16.001435
- [10] O.H.W. Siegmund, "Preconditioning of microchannel-plate stacks", *Proc. SPIE 1072, Image Intensification*, April 1989, pp. 111-118. doi:10.1117/12.952545
- [11] E.H. Eberhardt, "Gain model for microchannel plates", *Appl. Opt.*, vol. 18, no. 9, May 1979, pp. 1418-1423. doi:10.1364/AO.18.001418
- [12] J.L. Wiza, "Microchannel plate detectors", *Nucl. Instrum. Methods*, vol. 162, 1979, pp. 587-601. doi:10.1016/0029-554X(79)90734-4
- [13] T. Gys, "Micro-channel plates and vacuum detectors", *Nucl. Instrum. Methods Phys. Res., Sect. A*, vol. 787, July 2015, pp.254-260. doi:10.1016/j.nima.2014.12.044
- [14] J.M. Grant, "Noise problems in continuous channel electron multipliers", in *Proc. NASA ERD, Image Intensifier Symposium*, October 1961, Fort Belvoir, VA, USA, p. 63. https://ntrs.nasa.gov/api/citations/19620004873/downloads/19620004873.pdf
- [15] J.P. Rager and J.F. Renaud, "The use of a microchannel electron multiplier in spectroscopic instrumentation, involving frequent vacuum breaking", *Rev. Sci. Instrum.*, vol. 45, no. 7, July 1974, pp. 922-926. doi:10.1063/1.1686769
- [16] A. Chumikov, V. Cheptsov and N. Managadze, "Micro-channel plate detector gain decrease through storage under environmental conditions", *IEEE Trans. Instrum. Meas.*, vol. 72, 2023, p. 7003208. doi:10.1109/TIM.2023.3265633
- [17] N. Grifflits, S. Airiau and O. Siegmund, "In-flight performance of the SUMER microchannel plate detectors", *Proc. SPIE 3445, EUV, X-Ray, and Gamma-Ray Instrumentation for Astronomy IX*, Nov. 1998, pp. 566-577. doi:10.1117/12.330312
- [18] J. De Keyser *et al.*, "Position-dependent microchannel plate gain correction in Rosetta's ROSINA/DFMS mass spectrometer", *Int. J. Mass Spectrom.*, vol. 446, 2019, p. 116232. doi:10.1016/j.ijms.2019.116232
- [19] R.F. Malina and K.R. Coburn, "Comparative lifetesting results for microchannel plates in windowless EUV photon detectors", *IEEE Trans. Nucl. Sci.*, vol. 31, no. 1, Feb. 1984, pp. 404-407. doi:10.1109/TNS.1984.4333287
- [20] A. Lehmann *et al.*, "Recent developments with microchannel-plate PMTs", *Nucl. Instrum. Methods Phys. Res., Sect. A*, vol. 876, 2017, pp. 42-47. doi:10.1016/j.nima.2016.12.06
- [21] G.W. Fraser, J.F. Pearson and J.E. Lees, "Evaluation of long life (L²) microchannel plates for x-ray photon counting", *IEEE Trans. Nucl. Sci.*, vol. 35, no. 1, Feb. 1988, pp. 529-533. doi:10.1109/23.12779